

## Amendment and Response

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Serial No.: 09/651,702

Confirmation No.: 2471

Filed: August 30, 2000

For: SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL AND METHODS OF USING SAME

In the Claims

Please add new claims 49-54. The new claims are provided below in clean form.

For convenience, all pending claims, including those added hereby, are provided in Appendix A.

49. (New) A composition comprising sulfur trioxide ( $\text{SO}_3$ ) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

50. (New) A composition comprising sulfur trioxide ( $\text{SO}_3$ ) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from an object.

51. (New) A composition comprising:

a first component selected from the group consisting of carbon dioxide ( $\text{CO}_2$ ), ammonia ( $\text{NH}_3$ ),  $\text{H}_2\text{O}$ , nitrous oxide ( $\text{N}_2\text{O}$ ), carbon monoxide ( $\text{CO}$ ), nitrogen ( $\text{N}_2$ ), helium ( $\text{He}$ ), neon ( $\text{Ne}$ ), argon ( $\text{Ar}$ ), krypton ( $\text{Kr}$ ), and xenon ( $\text{Xe}$ );

E2 a second component selected from the group consisting of sulfur dioxide ( $\text{SO}_2$ ), nitrous oxide ( $\text{N}_2\text{O}$ ),  $\text{NO}$ ,  $\text{NO}_2$ , ozone ( $\text{O}_3$ ), hydrogen peroxide ( $\text{H}_2\text{O}_2$ ),  $\text{F}_2$ ,  $\text{Cl}_2$ ,  $\text{Br}_2$ , and oxygen ( $\text{O}_2$ ); and sulfur trioxide ( $\text{SO}_3$ ) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

52. (New) A composition comprising sulfur trioxide ( $\text{SO}_3$ ) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

53. (New) A composition comprising sulfur trioxide ( $\text{SO}_3$ ) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

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54. (New) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO<sub>2</sub>), ammonia (NH<sub>3</sub>), H<sub>2</sub>O, nitrous oxide (N<sub>2</sub>O), carbon monoxide (CO), nitrogen (N<sub>2</sub>), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

a second component selected from the group consisting of sulfur dioxide (SO<sub>2</sub>), nitrous oxide (N<sub>2</sub>O), NO, NO<sub>2</sub>, ozone (O<sub>3</sub>), hydrogen peroxide (H<sub>2</sub>O<sub>2</sub>), F<sub>2</sub>, Cl<sub>2</sub>, Br<sub>2</sub>, and oxygen (O<sub>2</sub>); and sulfur trioxide (SO<sub>3</sub>) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.